

CLAIMS

1. A polishing composition comprising hydroxyethyl cellulose, water and abrasive grains,  
wherein the hydroxyethyl cellulose has a molecular weight of 500,000 or more and 1,500,000 or less;  
the mass ratio of the hydroxyethyl cellulose to the abrasive grains is 0.0075 or more and 0.025 or less; and  
a content of the hydroxyethyl cellulose is 0.075% by mass or more and 0.15% by mass or less.
2. The polishing composition according to claim 1, wherein the abrasive grains are contained in an amount of 5% by mass or more and 20% by mass or less.
3. The polishing composition according to claim 2, further comprising ammonia.
4. The polishing composition according to claim 3, wherein the ammonia is contained in an amount of 0.1 % by mass or more and 1.0% by mass or less.
5. The polishing composition according to claim 1, further comprising ammonia.
6. The polishing composition according to claim 5, wherein the ammonia is contained in an amount of 0.1 % by mass or more and 1.0% by mass or less.